

REMARKS

Claims 1-3, 9 and 17 are pending. By this Amendment, claims 1 and 17 are amended. Reconsideration based on the above amendments and the following remarks is respectfully requested.

Applicants thank the Examiner for the telephone conference on September 12 indicating that claim 1 would be allowable if further amended. As suggested by the Examiner, claim 1 has been amended to recite "wherein a shape of an outer edge of said ion shield member is tapered, so as to prevent separation defect in the semi-conductor substrate main body." Similar changes have also been made to claim 17.

I. The Claims Define Allowable Subject Matter

The Office Action rejects claims 1-3 under 35 U.S.C. §103(a) as unpatentable over U.S. Patent No. 5,494,835 to Bruel ("Bruel '835") in view of U.S. Patent No. 5,374,564 to Bruel ("Bruel '564") and/or Japanese Patent No. 4-025114. The Office Action rejects claim 9 under 35 U.S.C. §103(a) as unpatentable over Bruel '835 in view of Bruel '564 and/or JP '114 and further in view of U.S. Patent No. 6,271,101 to Fukunaga. Claim 17 is rejected under 35 U.S.C. §103(a) as unpatentable over Bruel '835 in view of Bruel '564 and/or Japanese Patent No. 5-313195 ("JP '195"). These rejections are respectfully traversed.

As mentioned above, claim 1 has been amended in accordance with the Examiner's suggestion of September 12, 2003. This Amendment is believed to overcome the rejection 35 U.S.C. §103(a) as applied in the October 6, 2003 Office Action. As argued in the Amendment filed June 11, 2003, Bruel '835 and Bruel '564 do not teach or suggest an ion shield member that is tapered to prevent separation defect in the semi-conductor substrate main body. The Office Action asserts that JP '114 teaches the use of tapered sidewalls as shown in Fig. 2. However, the English abstract of JP '114 specifically states an esterification reaction that is generated between the resist film and the photosensitizer so as to achieve the

angle between the sidewall of the pattern and a substrate to be 90° or thereabout. Hence, JP '114 teaches away from having a tapered wall by substantially achieving a 90° angle. Fig. 2 of JP '114 shows problems in the conventional art of having tapered walls. Therefore, one skilled in the art would not be motivated to have tapered walls based on the teaching of JP '114. As such, claim 1 is believed to contain allowable subject matter as being non-obvious and patentably distinct over the applied art.

In addition, claim 17 has been amended to recite, *inter alia*, a shape of an outer edge of said ion shield member is tapered, so as to prevent separation defect in the semi-conductor substrate main body. As mentioned above, Bruel '835 and Bruel '564 do not teach or suggest a tapered outer edge of the ion shield member. In addition, JP '195 does not overcome the deficiencies of Bruel '835 and Bruel '564. Instead, JP '195 teaches a reduction in the power consumption of an integrated circuit and to eliminate a leak current due to a parasitic channel. Therefore, the combination of Bruel '835 in view of Bruel '564 and/or JP '195 teaches one skilled in the art away from the ion shield member having an outer tapered edge as disclosed in claim 17 of the application.

In addition, dependent claims 2, 3 and 9 are believed to contain allowable subject matter for at least the reasons discussed above and for the additional features they recite.

II. CONCLUSION

In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 1-3, 9 and 17 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



James A. Oliff
Registration No. 27,075

Ian R. Vallejo
Registration No. 53,714

JAO:IRV/dap

Date: January 6, 2004

OLIFF & BERRIDGE, PLC
P.O. Box 19928
Alexandria, Virginia 22320
Telephone: (703) 836-6400

**DEPOSIT ACCOUNT USE
AUTHORIZATION**

Please grant any extension
necessary for entry;
Charge any fee due to our
Deposit Account No. 15-0461